Application No. 10/664,355 Amendment dated July 10, 2006 After Final Office Action of May 8, 2006

## Docket No.: 2185-0698P

## AMENDMENTS TO THE CLAIMS

 (Currently amended) A negative type resist composition comprising [alkali soluble resin,] polyvinyl phenol-based resin in which the phenolic hydroxyl group is partially alkyletherified, acid generator, crosslinking agent, and a basic compound represented by the following formula (I)

wherein, A represents sulfide group  $\underline{o}$ t, disulfide group [or bivalent aliphatic hydrocarbon residue which may be optionally interrupted by imino group, sulfide group, or disulfide group,] X represents nitrogen atom [or  $C(NH_2)$ ], and  $R^1$  and  $R^2$  independently represent hydrogen or alkyl [provided that, when X represents  $C(NH_2)$ , A represents sulfide group or disulfide group].

2. (Original) The negative type resist composition according to claim 1, wherein the basic compound of the formula (I) is represented by the following formula (Ia):

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wherein, A, X, R<sup>1</sup> and R<sup>2</sup> are the same as defined in claim 1, and the marks, "}" and "{", indicate that A is positioned on 3-position, or 4-position on the six-membered rings with respect to X.

- (Canceled)
- (Canceled)

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- (Canceled)
- (Canceled)
- 7. (Previously Presented and Amended) The negative type resist composition according to [claim 1], wherein the basic compound of formula [lb] (1) is selected from 4,4'-dipyridylsulfide and 4,4'-dipyridyldisulfide.
  - (Canceled)
- (Original) The negative type resist composition according to claim 1, wherein the acid generator is a sulfonic ester of N-hydroxyimide compound.
- 10. (Currently Amended) The negative type resist composition according to claim 1.2. 7. or 9, wherein composition ratio of the basic compound of formula (I) is between 0.02 and 1 wt %, based on the total solid content in the composition.

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- (Cancelled)
- 12. (Cancelled)
- 13. (Cancelled)